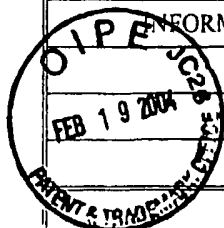


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INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Applicants			
(Use several sheets if necessary)				Lairson et al.			
				Filing Date		Group	
				12/5/03		Unknown	
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*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
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<i>PR</i>	AD	5,476,691	12/1993	Komvopoulos et al.	427	527	
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<i>PR</i>	AK	5,837,357	11/1998	Matsuo et al.	428	212	
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		Document	Date	Country	Class	Subclass	Translation
							Yes No
<i>PR</i>	AL	0 547 820	6/1993	EP			
<i>PR</i>	AM	62-183022	8/1987	Japan			
<i>PR</i>	AN	1-320622	12/1989	Japan			
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<i>PR</i>	AR	Anders, et al., "Mechanical Properties of Amorphous Hard Carbon Films Prepared by Cathodic Arc Deposition", Mat. Res. Soc. Symp. Proc. Vol. 383, 1995, pp. 453-458					
<i>PR</i>	AS	Sanders, et al., "Coating Technology Based on the Vacuum Arc—A Review", IEEE Transactions on Plasma Science, Vol. 18, No. 6, December 1990, pp. 883-894					
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							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
<i>PH</i>	AL	9-44844	2/1997	Japan				
<i>PH</i>	AM	9-288818	11/1997	Japan				
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	AB						
	AC						
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	AE						
	AF						
	AG						
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	AI						
	AJ						
	AK						
Foreign Patent Documents							
							Translation
		Document	Date	Country	Class	Subclass	Yes No
<i>pm</i>	AL	11-39647	2/1999	Japan			
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